

Notice of References Cited	Application/Control No. 09/018,783	Applicant(s)/Patent Under Reexamination RITZDORF ET AL.	
	Examiner Thomas J. Magee	Art Unit 2811	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

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	V	S. Wolf, "Silicon Processing for the VLSI Era, Vol. 4: Deep-Submicron Process Technology," Lattice Press, Sunset Beach, CA. (2002), pp. 639-670.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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